IN THE CLAIMS

1. (Currently Amended) Acetoxymethylacenaphthylene of the following formula (1)[[.]]

$$CH_2$$
 CH_2
 CH_3
 CH_3

2. (Currently Amended) Hydroxymethylacenaphthylene of the following formula (2)[[.]]

$$CH_2$$
—OH

3. (Original) A polymer containing a structural unit of the following formula (3),

$$\begin{array}{c|c}
R^2 & R^3 \\
\hline
C & C
\end{array}$$

$$\begin{array}{c|c}
CH_2 & OR^1
\end{array}$$

wherein R¹ is a hydrogen atom and R² and R³ individually represent a monovalent atom or a monovalent organic group, the polymer having a polystyrene-reduced weight average molecular weight determined by gel permeation chromatography (GPC) in the range of 500 to 10,000.

- 4. (Original) An antireflection film-forming composition comprising the polymer of Claim 3 and a solvent.
 - 5. (Previously Presented) An antireflection film-forming composition comprising, a polymer having a structural unit of the following formula (4)

$$\begin{array}{c|c}
R^5 & H \\
C & C \\
C & H
\end{array}$$

$$\begin{array}{c|c}
CH_2 & OR^4
\end{array}$$
(4)

wherein R⁴ is a monovalent organic group selected from the group consisting of a phenyl group, an alkyl group, an alkenyl group, and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group, R⁵ is a monovalent atom or a monovalent organic group, and n is 0 or 1, and

a solvent.

6. (Previously Presented) An antireflection film-forming composition comprising, at least one polymer selected from the group consisting of: a polymer having a structural unit of the following formula (3)

$$\begin{array}{c|c}
R^2 & R^3 \\
\hline
CH_2 & OR^1
\end{array}$$
(3)

wherein R¹ is a hydrogen atom and R² and R³ individually represent a monovalent atom or a monovalent organic group and a structural unit of the following formula (4)

$$\begin{array}{c|c}
R^5 & H \\
C & C \\
C & H
\end{array}$$

$$\begin{array}{c|c}
CH_2 & OR^4
\end{array}$$
(4)

wherein R⁴ is a hydrogen atom or a monovalent organic group, R⁵ is a monovalent atom or a monovalent organic group, and n is 0 or 1; a polymer having a structural unit of the formula (3) and a structural unit of the following formula (5),

$$\begin{array}{c|c}
R^6 & R^7 \\
\hline
C & C
\end{array}$$
(5)

wherein R⁶ and R⁷ individually represent a monovalent atom or a monovalent organic group; and

a polymer having a structural unit of the formula (4) and a structural unit of the formula (5); and a solvent.

- 7. (Original) The antireflection film-forming composition according to Claim 4, further comprising an acid generator.
- 8. (Original) The antireflection film-forming composition according to Claim 5, further comprising an acid generator.
- 9. (Original) The antireflection film-forming composition according to Claim 6, further comprising an acid generator.
 - 10. (Canceled)
 - 11. (Previously Presented) An antireflection film-forming composition comprising: a polymer having a structural unit of the following formula (4):

$$\begin{array}{c|c}
R^5 & H \\
C & C \\
C & H
\end{array}$$

$$\begin{array}{c|c}
CH_2 & OR^4
\end{array}$$
(4)

wherein R⁴ is a hydrogen atom or a monovalent organic group and R⁵ is a monovalent atom or a monovalent organic group; and

a solvent.

12. (Previously Presented) The antireflection film-forming composition according to Claim 11, further comprising an acid generator.